

Notice of References Cited	Application/Control No. 10/714,807	Applicant(s)/Patent Under Reexamination HSHIEH ET AL.	
	Examiner Toniae M. Thomas	Art Unit 2822	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-2002/0096710 A1	07-2002	Inagawa et al.	257/330
	B	US-2002/0168821 A1	11-2002	Williams et al.	438/268
	C	US-5,100,829	03-1992	Fay et al.	438/54
	D	US-5,959,345	09-1999	Fruth et al.	257/605
	E	US-6,268,242 B1	07-2001	Williams et al.	438/237
	F	US-6,455,378 B1	09-2002	Inagawa et al.	438/270
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Wolf, Ph.D., Stanley, Richard N. Tauber, Ph.D., "Silicon Epitaxial Film Growth," Silicon Processing for the VLSI Era - Vol. 1: Process Technology, Lattice Press, 1986, page 124
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.